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PATENT ABSTRACTS OF JAPAN

(11)Publication number : 06-224154

(43)Date of publication of application : 12.08.1994

(51)Int.Cl.

H01L 21/302
C23F 4/00
H05H 1/46

(21)Application number : 05-010090

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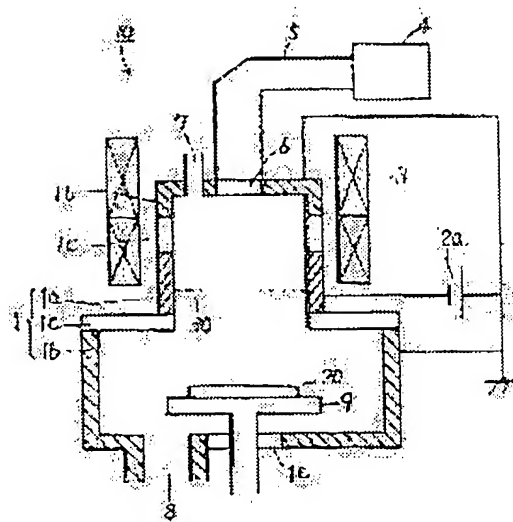
(22)Date of filing : 25.01.1993

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(54) PLASMA PROCESSING APPARATUS

(57)Abstract:

PURPOSE: To enhance uniformity of etching and anisotropy by eliminating uniformity of distribution of plasma potential, electron density, and ion density.
CONSTITUTION: An electromagnetic coil 3 and a microwave generating source 4 provided so as to generate a magnetic field inside a reaction container 1 and to introduce microwaves into it to make an ECR discharge take place in reactive gas inside the reaction container 1. A specimen pad 9, on which a wafer 20 is placed so as to be etched by plasma generated inside the container 1, is provided inside the container 1. The reaction contain 1 is provided with a first part 1a and second parts 1b insulated from the first part 1a by insulating parts 1c. A potential difference is given between the first part 1a and the second part 1b by a power source 2a.



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[Date of request for examination]

[Date of sending the examiner's decision of rejection]

[Kind of final disposal of application other than the examiner's decision of rejection or application converted registration]

[Date of final disposal for application]

[Patent number]

[Date of registration]

[Number of appeal against examiner's decision of rejection]

[Date of requesting appeal against examiner's decision of rejection]

[Date of extinction of right]

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